

Title (en)

METHOD AND DEVICE FOR PRODUCING METAL PROFILES HAVING A CLOSELY TOLERANCED CHAMBER DIMENSION

Title (de)

VERFAHREN UND VORRICHTUNG ZUR HERSTELLUNG VON METALLPROFILEN MIT ENG TOLERIERTEM KAMMERMAß

Title (fr)

PROCÉDÉ ET DISPOSITIF POUR LA FABRICATION DE PROFILÉS MÉTALLIQUES AVEC UNE DISTANCE ENTRE SEMELLES À TRÈS FAIBLE TOLÉRANCE

Publication

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Application

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Abstract (en)

[origin: WO2012155953A1] The invention relates to a method and to a device (10) for producing metal profiles (20) having two opposing profile flanges (21, 22, 23, 24), which have flange inner faces that are spaced apart from one another by a closely toleranced chamber dimension. In order to adjust the chamber dimension from an initial chamber dimension K0 to a desired final chamber dimension K1, the metal profile (20) is guided through the device (10), which forms working gaps between an inner working roller pair (11, 12, 13, 14) and outer support rollers (15, 16). The working rollers forming the inner working roller pair roll off one another in order to brace the forming forces exerted on the working roller pair by the flange inner faces.

IPC 8 full level

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